



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Koji NOZAKI et al.**

Group Art Unit: **1752**

Application Number: **10/623,679**

Examiner: **Amanda C. Walke**

Filed: **July 22, 2003**

Confirmation Number: **5083**

For: **RESIST PATTERN THICKENING MATERIAL, RESIST PATTERN
AND PROCESS FOR FORMING THE SAME, AND
SEMICONDUCTOR DEVICE AND PROCESS FOR
MANUFACTURING THE SAME**

Attorney Docket Number: **030891**

Customer Number: **38834**

INFORMATION DISCLOSURE STATEMENT
UNDER 37 C.F.R. 1.97(c)(2)

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

July 6, 2007

Sir:

Applicants direct the attention of the Patent and Trademark Office to the documents listed on the attached PTO/SB/08. A copy of each non- U.S. document is attached.

This Information Disclosure Statement is being submitted after issuance of a first official action on the merits and expiration of the three month period following the filing date or the entry of the national stage for the above-captioned application, but prior to issuance of either a final official action or a Notice of Allowance. A check is attached hereto which covers the **\$180.00** fee set forth in 37 C.F.R. §1.17(p).

07/09/2007 AWONDAF1 00000069 10623679

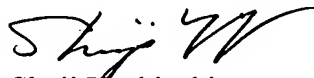
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Information Disclosure Statement under 1.97(c)(2)
Attorney Docket No. 030891
Serial No. 10/623,679

If there are any fees due in connection with the filing of this paper, please charge Deposit
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Respectfully submitted,
WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP



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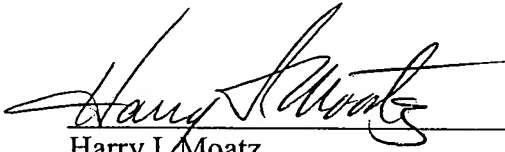
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Expires: July 7, 2010**



Harry I. Moatz
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Combined Form PTO/SB/08A&B <u>INFORMATION DISCLOSURE</u> <u>STATEMENT BY APPLICANT</u> (use as many sheets as necessary)		<i>Complete if Known</i>	
		Application Number	10/623,679
		Confirmation Number	5083
		Filing Date	July 22, 2003
		First Named Inventor	Koji NOZAKI et al.
		Art Unit	1752
Examiner Name	Amanda C. Walke		
Attorney Docket Number	030891		
Sheet	1	of	1

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
		Number	Kind Code ² <i>(if known)</i>		
		US			
		US			
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FOREIGN PATENT DOCUMENTS							
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NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.	Translation ⁶
	1	Takeo Ishibashi et al.; Advanced Micro-Lithography Process with Chemical Shrink Technology; The Japan Society of Applied Physics; Japanese Journal of Applied Physics, Vol. 40 (2001), January 15, 2001, pp. 419-425;	
	2	Mamoru Terai et al.; Below 70-nm Contact Hole Pattern with RELACS Process on ArF Resist; Advances in Resist Technology and Processing XX, Theodore H. Fedynyshyn, Editor; Proceedings of SPIE Vol. 5039 (2003), June 12, 2003	
	3	Mamoru Terai et al.; Newly Developed Resolution Enhancement Lithography Assisted by Chemical Shrink Process and Materials for Next-Generation Devices; The Japan Society of Applied Physics; Japanese Journal of Applied Physics, Vol. 45, No. 6B (2006), June 20, 2006, pp. 5354-5358	

Examiner Signature		Date Considered	
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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